

IEUVI Resist TWG agenda
Sunday September 10th, 2017
Monterey Marriott, San Carlos Room



Start: 9AM

Paolo Gargini - Welcome

Yu-Jen Fan (ASML) – meeting agenda and organization

Toru Fujimori (Fujifilm) “Recent progress of CAR materials for EUV lithography”

Alex Robinson (U. Birmingham) “Multi-trigger resist”

Greg Blachut (LAM) “Self-immolating behavior enables a chemically-amplified photoresist without acid catalysis”

Anindarupa Chunder (GlobalFoundries) “Challenges in next generation EUV resists and processes”

Break: 10:30

Eishi Shiobara (EIDEC) “The update of resist outgas testing at EIDEC”

Oleg Kostko (LBNL) “Novel ways to probe EUV radiation chemistry”

Greg Denbeaux (SUNY Polytechnic) “Polymer effects on PAG acid yield in EUV resists”

Sang Jin Cho (FST) “The updated EUV pellicle development status of FST”

Finish: Noon